

## ABSTRACT OF THE DISCLOSURE

An optical element and a manufacturing method therefor, an exposure apparatus, and a device manufacturing method that can reduce the effect of intrinsic  
5 birefringence under high NA conditions. According to an optical element as one aspect of the present invention, an angle between a  $[0\ 0\ 1]$  axis of an isometric crystal and an optical axis is less than  $10^\circ$ , and preferably  $0^\circ$ .